

## PATENT ABSTRACTS OF JAPAN

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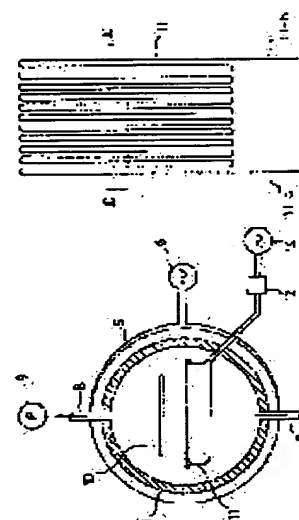
(54) PLASMA CVD DEVICE

(57)Abstract:

PURPOSE: To intensify and uniform electric field intensity in the vicinity of an electrode and to produce an amorphous silicon thin film having large area at high velocity by utilizing the zigzag plane-shaped coil electrode as the electrode for discharge.

CONSTITUTION: A zigzag plane-shaped coil electrode 11 having a structure wherein one piece of wire rod is alternately bent into a U-shape is arranged in a reaction vessel 1. When voltage is impressed to this electrode 11 via an impedance matching circuit 12 from a high-frequency power source 14, glow discharge plasma is generated around the electrode 11. When observing this state, nearly uniform luminous intensity is shown between the electrode 11 and a base plate 10.

Thereby an amorphous silicon thin film stuck on the surface of the base plate 10 is made uniform in the distribution of film thickness thereof.



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